Forming a second MQW active layer over a substrate —1

Forming an n-GaN based layer over the second MQW active layer —2

Forming a first MQW active layer over the n-GaN based layer —3

Forming a p-DBR over the first MQW active layer —4

Forming a p-GaN based layer over the p-DBR —5

Coating a metal reflector over a bottom side of the substrate —6

FIG. 1

FIG. 2

101

P⁺-GaN-based material	— 161
P⁻-AlGaN/GaN DBR	— 151
InGaN/GaN 1st MQW	— 141
n⁻-GaN	— 131
InGaN/GaN 2nd MQW	— 121
GaN(buffer layer)	— 111
Sapphire(substrate)	— 101'
metal reflector	— 191

221

FIG. 3

111 {
HT-GaN
LT-GaN
}

FIG. 3A

R:Red	O:Orange
B:Blue	P:Purple
G:Green	Pk:Pink
Y:Yellow	W:Write

FIG. 4

Forming a second MQW active layer over a substrate ⌐1

Forming an n-GaN based layer over the second MQW active layer ⌐2

Forming a first MQW active layer over the n-GaN based layer ⌐3

Forming a p-DBR over the first MQW layer ⌐4

Forming a p-GaN based layer over the p-DBR ⌐5

Forming a TCL over the p-GaN based layer ⌐6'

Coating a metal reflector over the substrate ⌐7

FIG. 5

FIG. 6

<u>201</u>

TCL — 211
P$^+$-GaN-based material — 161
P-AIGaN/GaN DBR — 151
InGaN/GaN 1st MQW — 141
n-GaN — 131
InGaN/GaN 2nd MQW — 121
GaN(buffer layer) — 111
Sapphire(substrate) — 101'
metal reflector — 191

221

FIG. 7

Forming a second MQW active layer over a substrate ⌐1

Forming an n-GaN based layer over the second MQW layer ⌐2

Forming a first MQW active layer over the n-GaN based layer ⌐3

Forming a p-DBR over the first MQW active layer ⌐4

Forming a p-GaN based layer over the p-DBR ⌐5

Forming a TCL over the p-GaN layer ⌐6'

Forming a metal reflector over a bottom side of the substrate ⌐7

Coating a metal reflector over the substrate ⌐8

FIG. 8

Forming a n-DBR over a substrate	⌐1a

↓

Forming a second MQW active layer over the n-DBR	⌐2a

↓

Forming an n-GaN based layer over the second MQW active layer	⌐3a

↓

Forming a first MQW active layer over the n-GaN layer	⌐4a

↓

Forming a p-DBR over the first MQW active layer	⌐5a

↓

Forming a p-GaN based layer over the p-DBR	⌐6a

FIG. 9

39   30

37
36
35
34   34a
33
32
40
31
30a   30'

38

FIG. 10

300

P⁺-GaN-based material	—371

P^+-GaN-based material —371

P⁻-AlGaN/GaN DBR —361

InGaN/GaN 1st MQW —351

n⁻-GaN —341

n-AlGaN/GaN DBR —331

InGaN/GaN 2nd MQW —321

GaN(buffer layer) —311

Sapphire(substrate) —301

441 {361, 351, 341, 331, 321}

FIG. 11

311 {
HT-GaN
LT-GaN
}

FIG. 11A

| Forming a n-DBR over a substrate | ⌐1a |

↓

| Forming a second MQW active layer over the n-DBR | ⌐2a |

↓

| Forming an n-GaN based layer over the second MQW active layer | ⌐3a |

↓

| Forming a first MQW layer over the n-GaN based layer | ⌐4a |

↓

| Forming a p-DBR over the first MQW active layer | ⌐5a |

↓

| Forming a p-GaN based layer over the p-DBR | ⌐6a |

↓

| Forming a TCL over the p-GaN based layer | ⌐7a |

FIG. 12

FIG. 13

TCL		~401
P⁺-GaN-based material		~371
P-AIGaN/GaN DBR		~361
InGaN/GaN 1st MQW		~351
n-GaN		~341
n-AIGaN/GaN DBR		~331
InGaN/GaN 2nd MQW		~321
GaN(buffer layer)		~311
Sapphire(substrate)		~301

The layers 361, 351, 341, 331, 321 are bracketed together and labeled 421.

P^+-GaN-based material ~371

FIG. 14

Forming a n-DBR over a substrate ⌐1a

↓

Forming a second MQW active layer over the n-DBR ⌐2a

↓

Forming an n-GaN based layer over the second MQW active layer ⌐3a

↓

Forming a first MQW layer over the n-GaN based layer ⌐4a

↓

Forming a p-DBR over the first MQW active layer ⌐5a

↓

Forming a p-GaN based layer over the p-DBR ⌐6a

↓

Forming a TCL over the p-GaN based layer ⌐7a

↓

Subjecting the TCL to a surface treatment ⌐8a

FIG. 15

FIG. 16